CLAIMS

- 1. An apparatus for generating X-rays by irradiating a target with an electron beam, comprising vibration applying means for vibrating said target in directions parallel to a surface thereof.
- 2. An apparatus as defined in claim 1, wherein said vibration applying means is arranged to vibrate said target so that said electron beam has a colliding spot describing, on said target, one of a linear track, a circular track, and a two-dimensional shape including zigzag and rectangular shapes.

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3. An apparatus as defined in claim 1, further comprising the vibration controller for controlling said vibration applying means based on one of a tube voltage, a tube current, an electron beam diameter, and a temperature measured adjacent a spot of electron beam collision.

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4. An apparatus as defined in claim 3, wherein said vibration controller is arranged to control the vibration amplitude more than the electron beam diameter and variable.

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- 5. An apparatus as defined in claim 3, wherein said vibration controller is arranged to make the vibration frequency variable.
- 5 6. An apparatus as defined in claim 1, wherein said vibration applying means includes a piezoelectric device.
- 7. An apparatus as defined in claim 6, wherein said piezoelectric device is integrated with a holder having saidtarget to define a closed space.
 - 8. An apparatus as defined in claim 1, further comprising flexures for attaching and supporting said holder.
- 15 9. An apparatus as defined in claim 8, wherein said flexures are made by electrical discharge machining.

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- 10. An apparatus as defined in claim 1, wherein said target is vacuum-sealed by rubber elements or flexures.
- 11. An apparatus as defined in claim 1, wherein said target has a thickness up to twice depth of electrons penetration calculated from a tube voltage and said target material.
- 25 12. An apparatus as defined in claim 1, wherein said vibra-

tion applying means is arranged to displace said target.

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- 13. An apparatus as defined in claim 1, wherein said vibration applying means is disposed in an bore in which said target is located.
- 14. An apparatus as defined in claim 8, wherein said flexures are shaped thin in a direction of vibration of said target, and thick in a direction perpendicular to the direction of vibration.
- 15. An apparatus as defined in claim 1, wherein said target has a thickness corresponding to a diameter of collision of said electron beam.

16. An apparatus as defined in claim 1, wherein said target is disposed at an angle to said electron beam.